

**ELECTRONICALLY FILED ON 05 OCTOBER 2007**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of inventor(s):

Michel Luc Cote et al.

Application No. 10/799,073

Confirmation No. 8538

Filing Date: 12 March 2004

**Title: Design and Layout of Phase Shifting Photolithographic Masks**

Group Art Unit: 1756

Examiner: Stephen D. Rosasco

**CUSTOMER NO. 30437**

**MAIL STOP ISSUE FEE**

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

**SUBMISSION OF PRIOR ART AFTER NOTICE OF ALLOWANCE**

Sir:

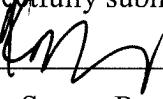
Applicants submit the below-listed prior art to be placed in the record:

- U.S. Patent No. 6,004,701 issued to Uno et al.
- U.S. Patent No. 6,391,501 issued to Ohnuma
- Japanese Publication No. 11-212247 dated 06 August 1999
- Japanese Publication No. 10-326007 dated 18 December 1998

The Commissioner is hereby authorized to charge any fee determined to be due in connection with this communication, or credit any overpayment, to our Deposit Account No. 50-0869 (NMTI 1002-26).

Dated: 5 Oct. 2007

Respectfully submitted,



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